

c) Amendments to the Claims

Please cancel Claims 5-11 without prejudice or disclaimer of the subject matter therein. Please add new Claim 12 as follows. The status of all the claims is listed below.

1. (Original) A plasma treatment method of treating the surface of a treatment target substrate by utilizing glow discharge produced by supplying high-frequency power into an inside-evacuated reactor through a high-frequency power supply means, wherein;

a plurality of impedance regulation means for regulating impedances on the side of the reactor and on the side of the high-frequency power supply means are provided correspondingly to the impedances of a plurality of reactors, and the high-frequency power is supplied into the reactors via the impedance regulation means corresponding to the reactors.

2. (Original) The plasma treatment method according to claim 1, wherein the impedance is regulated by electrostatic capacitance.

3. (Original) The plasma treatment method according to claim 1, wherein the impedance is regulated by inductance coefficient.

4. (Original) The plasma treatment method according to claim 1, wherein the high-frequency power supply means and each of the reactors are provided separably, and, while the plasma treatment is made in respect of a first reactor to which the high-frequency power supply means has been connected, a second reactor having impedance different from the first reactor is made ready for the next plasma treatment.

5-11. (Cancelled)

12. (New) A plasma treatment apparatus comprising:

a plurality of reactors each having an evacuable inside where at least one treatment substrate is set in, and having impedances different from each other;

a high-frequency power supply means for supplying high-frequency power into each reactor having been inside-evacuated, to cause glow discharge to take place in the reactor, wherein each of the reactors and the high-frequency power supply means are provided separably;

a plurality of impedance regulation means provided correspondingly to the impedances of each of the reactors in order to regulate impedances on the side of each reactor and on the side of the high-frequency power supply means; and

a moving means for moving the reactors.